

ABSTRACT OF THE DISCLOSURE

Methods and systems for inspecting a reticle are provided. A method may include forming an aerial image of the reticle with an inspection system at a wavelength different
5 from a wavelength of an exposure system. The method may also include correcting the aerial image for differences between modulation transfer functions (MTF) of the inspection system and the exposure system. In this manner, the corrected aerial image may be substantially equivalent to an image of the reticle that would be printed onto a specimen by the exposure system at the wavelength of the exposure system. In addition,
10 the method may include detecting defects on the reticle using the corrected aerial image. The detected defects may include approximately all of the defects that would be printed onto a specimen by the exposure system using the reticle.